

# Guojin Chen





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Last updated on September 7, 2024

## Education

<b>Ph.D. in Computer Science</b> , <i>Chinese University of Hong Kong</i>	2021 – Present
Supervisor : Prof. Bei Yu	
<b>M.S. in Computer Science</b> , <i>Chinese University of Hong Kong</i>	2019 – 2020
<b>B.S. in Computer Science</b> , <i>Huazhong University of Science and Technology</i>	2015 – 2019

## Experiences

 <b>DeepMind</b> <b>Google DeepMind</b> , <i>Ph.D. Student Researcher</i>	2024.07 – Present Mountain view, CA
 <b>NVIDIA</b> , <i>Research Scientist Intern</i> (Mentor & Manager. Haoyu Yang & Mark Ren)	2024.04 – 2024.07 Austin, TX
 <b>University of Texas at Austin</b> , <i>Visiting Scholar</i> (Supervisor : Prof. David Z. Pan)	2023.08 – 2024.4 Austin, TX
 <b>Tencent</b> , <i>Research Intern</i>	2018 – 2019 Shenzhen, China

## Research Interests

- Design for manufacturing: computational lithography, mask optimization, OPC, SMO.
- Deep learning in VLSI design: physics-informed networks for EDA problems
- Optimization: bi-level & multi-level optimization, GPU acceleration, level-set optimization.
- Scaling deep learning: large language models, LLM on EDA, large-scale layout representation learning.

## Publications [Google Scholar; 220+ citations, h-index: 8+]

Representative publications that I am a primary author on are **highlighted**.

### Conference papers

- [C16] Differentiable Edge-based OPC  
**Guojin Chen**, Haoyu Yang, Haoxing Ren, Bei Yu, and David Z. Pan  
(**ICCAD 2024**) *Proceedings of the 43rd International Conference on Computer-Aided Design*
- [C15] Efficient Bilevel Source Mask Optimization  
**Guojin Chen**, Hongquan He, Peng Xu, Hao Geng, and Bei Yu  
(**DAC 2024**) *ACM/IEEE Design Automation Conference*
- [C14] Fracturing-aware Curvilinear ILT via Circular E-beam Mask Writer  
Xinyun Zhang, Su Zheng, **Guojin Chen**, Binwu Zhu, Hong Xu, and Bei Yu  
(**DAC 2024**) *ACM/IEEE Design Automation Conference*
- [C13] Performance-driven Analog Routing via Heterogeneous 3DGNN and Potential Relaxation  
Peng Xu, **Guojin Chen**, Keren Zhu, Tinghuan Chen, Tsung-Yi Ho, and Bei Yu  
(**DAC 2024**) *ACM/IEEE Design Automation Conference*
- [C12] Open-Source Differentiable Lithography Imaging Framework  
**Guojin Chen**, Hao Geng, Bei Yu, and David Z. Pan  
(**SPIE 2024**) *SPIE Advanced Lithography + Patterning*
- [C11] AlphaSyn: Logic Synthesis Optimization with Efficient Monte Carlo Tree Search  
Zehua Pei, Fangzhou Liu, Zhuolun He, **Guojin Chen**, Haisheng Zheng, Keren Zhu, and Bei Yu  
(**ICCAD 2023**) *Proceedings of the 42th International Conference on Computer-Aided Design*
- [C10] Physics-Informed Optical Kernel Regression Using Complex-valued Neural Fields  
**Guojin Chen**, Zehua Pei, Haoyu Yang, Yuzhe Ma, Bei Yu, and Martin Wong  
(**DAC 2023**) *ACM/IEEE Design Automation Conference* (**Best score in DFM track.**)

- [C9] DiffPattern: Layout Pattern Generation via Discrete Diffusion  
Zixiao Wang, Yunheng Shen, Wenqian Zhao, Yang Bai, **Guojin Chen**, Farzan Farnia, and Bei Yu  
(**DAC 2023**) *ACM/IEEE Design Automation Conference*
- [C8] GPU-accelerated Matrix Cover Algorithm for Multiple Patterning Layout Decomposition  
**Guojin Chen**, Haoyu Yang, and Bei Yu  
(**SPIE 2023**) *DTCO and Computational Patterning II*
- [C7] Efficient Point Cloud Analysis Using Hilbert Curve.  
Wanli Chen, Xinge Zhu, **Guojin Chen**, and Bei Yu  
(**ECCV 2022**) *European Conference on Computer Vision*
- [C6] AdaOPC: A Self-Adaptive Mask Optimization Framework For Real Design Patterns  
Wenqian Zhao, Xufeng Yao, Ziyang Yu, **Guojin Chen**, Yuzhe Ma, Bei Yu, and Martin Wong  
(**ICCAD 2022**) *Proceedings of the 41th International Conference on Computer-Aided Design*
- [C5] LayoutTransformer: Generating Layout Patterns with Transformer via Sequential Pattern Modeling  
Liangjian Wen, Yi Zhu, Lei Ye, **Guojin Chen**, Bei Yu, Jianzhuang Liu, and Chunjing Xu  
(**ICCAD 2022**) *Proceedings of the 41th International Conference on Computer-Aided Design*
- [C4] DevelSet: Deep Neural Level Set for Instant Mask optimization  
**Guojin Chen**, Ziyang Yu, Hongduo Liu, Yuzhe Ma, and Bei Yu  
(**ICCAD 2021**) *Proceedings of the 40th International Conference on Computer-Aided Design*
- [C3] Learning Point Clouds in EDA.  
Wei Li, **Guojin Chen**, Haoyu Yang, Ran Chen, and Bei Yu  
(**ISPD 2021**) *ACM International Symposium on Physical Design*
- [C2] DAMO: Deep Agile Mask Optimization for Full Chip Scale  
**Guojin Chen**, Wanli Chen, Yuzhe Ma, Haoyu Yang, and Bei Yu  
(**ICCAD 2020**) *Proceedings of the 39th International Conference on Computer-Aided Design*
- [C1] A GPU-enabled Level Set Method for Mask Optimization  
Ziyang Yu, **Guojin Chen**, Yuzhe Ma, and Bei Yu  
(**DATE 2020**) *IEEE/ACM Proceedings Design, Automation and Test in Europe*

## Journal papers.....

- [J6] DeepOTF: Learning Equations-constrained Prediction for Electromagnetic Behavior  
Peng Xu, Siyuan Xu, Tinghuan Chen, **Guojin Chen**, Tsung-Yi Ho, and Bei Yu  
(**TODAES 2024**) *ACM Trans. Des. Autom. Electron. Syst.*
- [J5] Ultra-Fast Source Mask Optimization via Conditional Discrete Diffusion  
**Guojin Chen**, Zixiao Wang, Bei Yu, David Z. Pan, and Martin D.F. Wong  
(**TCAD 2024**) *IEEE Transactions on Computer-Aided Design of Integrated Circuits and Systems*
- [J4] L2O-ILT: Learning to Optimize Inverse Lithography Techniques  
Binwu Zhu, Su Zheng, Ziyang Yu, **Guojin Chen**, Yuzhe Ma, Fan Yang, Bei Yu, and Martin Wong  
(**TCAD 2023**) *IEEE Transactions on Computer-Aided Design of Integrated Circuits and Systems*
- [J3] A GPU-Enabled Level-Set Method for Mask Optimization  
Ziyang Yu, **Guojin Chen**, Yuzhe Ma, and Bei Yu  
(**TCAD 2023**) *IEEE Transactions on Computer-Aided Design of Integrated Circuits and Systems*
- [J2] DevelSet: Deep Neural Level Set for Instant Mask optimization  
**Guojin Chen**, Ziyang Yu, Hongduo Liu, Yuzhe Ma, and Bei Yu  
(**TCAD 2023**) *IEEE Transactions on Computer-Aided Design of Integrated Circuits and Systems*
- [J1] DAMO: Deep Agile Mask Optimization for Full-Chip Scale  
**Guojin Chen**, Wanli Chen, Qi Sun, Yuzhe Ma, Haoyu Yang, and Bei Yu  
(**TCAD 2022**) *IEEE Transactions on Computer-Aided Design of Integrated Circuits and Systems*

Preprints.....

[P1] LLM-Enhanced Bayesian Optimization for Efficient Analog Layout Constraint Generation  
Guojin Chen, Keren Zhu, Seunggeun Kim, Hanqing Zhu, Yao Lai, Bei Yu, and David Z Pan  
(arXiv 2024) arXiv preprint arXiv:2406.05250

Open Source Repositories

1. TorchOPC/TorchLitho	★140	Differentiable computational lithography with PyTorch	2024
2. dekura/LLANA	★9	LLM-Enhanced Bayesian Optimization for Efficient Analog Constraint Generation	2024
3. OpenOPC/OpenILT	★106	Open-source inverse lithography technology (ILT) framework	2023
4. ai4eda/awesome-AI4EDA	★112	A curated paper list of existing AI for EDA studies.	2023

Awards

Ph.D. Studentship	2021 – 2025
By Chinese University of Hong Kong, 2021-2025	
Outstanding Graduate	2019
By Huazhong University of Science and Technology	

Professional Activities

Paper Review / External Review.....

Neural Information Processing Systems (NeurIPS)	2023-2024
Design Automation Conference (DAC)	2021-2024
AAAI Conference on Artificial Intelligence (AAAI)	2022-2025
IEEE Transactions on Computer-Aided Design of Integrated Circuits and Systems (TCAD)	2022-2024